Timo Hatanp

List of Publications by Citations

51 papers	1,380 citations	23 h-index	36 g-index
54 ext. papers	1,531 ext. citations	5.6 avg, IF	4.22 L-index

#	Paper	IF	Citations
51	Atomic layer deposition of metal tellurides and selenides using alkylsilyl compounds of tellurium and selenium. *Journal of the American Chemical Society*, **2009**, 131, 3478-80	16.4	132
50	Lithium Phosphate Thin Films Grown by Atomic Layer Deposition. *Journal of the Electrochemical Society*, **2012**, 159, A259-A263	3.9	77
49	Atomic Layer Deposition of Crystalline MoS2 Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. *Advanced Materials Interfaces*, **2017**, 4, 1700123	4.6	75
48	Bismuth precursors for atomic layer deposition of bismuth-containing oxide films. *Journal of Materials Chemistry*, **2004**, 14, 3191-3197		71
47	Precursors as enablers of ALD technology: Contributions from University of Helsinki. *Coordination Chemistry Reviews*, **2013**, 257, 3297-3322	23.2	63
46	Study of a novel ALD process for depositing MgF2 thin films. *Journal of Materials Chemistry*, **2007**, 17, 5077		59
45	Atomic layer deposition of Ge2Sb2Te5 thin films. *Microelectronic Engineering*, **2009**, 86, 1946-1949	2.5	58
44	Effects of spray drying on physicochemical properties of chitosan acid salts. *AAPS PharmSciTech*, **2011**, 12, 637-49	3.9	50
43	Synthesis and characterisation of cyclopentadienyl complexes of barium: precursors for atomic layer deposition of BaTiO3. *Dalton Transactions*, **2004**, 1181-8	4.3	47
42	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of Sb2Te3 and GeTe from (Et3Si)2Te and Chlorides. *Chemistry of Materials*, **2010**, 22, 1386-1391	9.6	46
41	Properties of [Mg2(thd)4] as a Precursor for Atomic Layer Deposition of MgO Thin Films and Crystal Structures of [Mg2(thd)4] and [Mg(thd)2(EtOH)2]. *Chemistry of Materials*, **1999**, 11, 1846-1852	9.6	44
40	Atomic Layer Deposition of Ferroelectric Bismuth Titanate Bi4Ti3O12 Thin Films. *Chemistry of Materials*, **2006**, 18, 3883-3888	9.6	43
39	Iridium metal and iridium oxide thin films grown by atomic layer deposition at low temperatures. *Journal of Materials Chemistry*, **2011**, 21, 16488		39
38	Study of bismuth alkoxides as possible precursors for ALD. *Dalton Transactions*, **2010**, 39, 3219-26	4.3	37
37	Study of amorphous lithium silicate thin films grown by atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2012**, 30, 01A106	2.9	35
36	Atomic Layer Deposition of PbI2 Thin Films. *Chemistry of Materials*, **2019**, 31, 1101-1109	9.6	34
35	(MeCp)Ir(CHD) and molecular oxygen as precursors in atomic layer deposition of iridium. *Journal of Materials Chemistry*, **2010**, 20, 7669		32

34	Electric and Magnetic Properties of ALD-Grown BiFeO3 Films. *Journal of Physical Chemistry C*, **2016**, 120, 7313-7322	3.8	25
33	Thermal Atomic Layer Deposition of Continuous and Highly Conducting Gold Thin Films. *Chemistry of Materials*, **2017**, 29, 6130-6136	9.6	25
32	Programming nanostructured soft biological surfaces by atomic layer deposition. *Nanotechnology*, **2013**, 24, 245701	3.4	25
31	Crystal structures and thermal properties of Ba(1,2,4-t-Bu3C5H2)2 and Sr(1,2,4-t-Bu3C5H2)2: Precursors for atomic layer deposition. *Journal of Organometallic Chemistry*, **2007**, 692, 5256-5262	2.3	25
30	Studies on Thermal Atomic Layer Deposition of Silver Thin Films. *Chemistry of Materials*, **2017**, 29, 2040-2045	9.6	23
29	Atomic layer deposition and characterization of Bi□Te□ thin films. *Journal of Physical Chemistry A*, **2015**, 119, 2298-306	2.8	23
28	Cycloheptatrienyl-Cyclopentadienyl Heteroleptic Precursors for Atomic Layer Deposition of Group 4 Oxide Thin Films. *Chemistry of Materials*, **2012**, 24, 2002-2008	9.6	22
27	The use of disaccharides in inhibiting enzymatic activity loss and secondary structure changes in freeze-dried □galactosidase during storage. *Pharmaceutical Research*, **2011**, 28, 540-52	4.5	22
26	Ancillary ligand effect on the properties of "Mg(thd)2" and crystal structures of [Mg(thd)2(ethylenediamine)]2, [Mg(thd)2(tmeda)], and [Mg(thd)2(trien)]. *Inorganic Chemistry*, **2001**, 40, 788-94	5.1	22
25	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. *Chemistry of Materials*, **2018**, 30, 3499-3507	9.6	21
24	Magnetic Properties of Polycrystalline Bismuth Ferrite Thin Films Grown by Atomic Layer Deposition. *Journal of Physical Chemistry Letters*, **2014**, 5, 4319-23	6.4	21
23	Intralanthanide Separation on Layered Titanium(IV) Organophosphate Materials via a Selective Transmetalation Process. *ACS Applied Materials & Interfaces*, **2018**, 10, 22083-22093	9.5	18
22	Atomic Layer Deposition of Materials for Phase-Change Memories. *ECS Transactions*, **2009**, 25, 399-407	1	17
21	Bismuth iron oxide thin films using atomic layer deposition of alternating bismuth oxide and iron oxide layers. *Thin Solid Films*, **2016**, 611, 78-87	2.2	16
20	Potential gold(I) precursors evaluated for atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 01B112	2.9	13
19	Alkylsilyl Compounds of Selenium and Tellurium: New Precursors for ALD. *ECS Transactions*, **2009**, 25, 609-616	1	13
18	Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 041506	2.9	12
17	Titanium alkylphosphate functionalised mesoporous silica for enhanced uptake of rare-earth ions. *Journal of Materials Chemistry A*, **2017**, 5, 23805-23814	13	12

16	(Et3Si)2Se as a precursor for atomic layer deposition: growth analysis of thermoelectric Bi2Se3. *Journal of Materials Chemistry C*, **2015**, 3, 4820-4828	7.1	12
15	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 020921	2.9	10
14	Bismuth(III) Alkoxide Catalysts for Ring-Opening Polymerization of Lactides and ?-Caprolactone. *Macromolecular Chemistry and Physics*, **2013**, 214, 707-715	2.6	9
13	Novel electroblowing synthesis of submicron zirconium dioxide fibers: effect of fiber structure on antimony(V) adsorption. *Nanoscale Advances*, **2019**, 1, 4373-4383	5.1	9
12	Scale-up of the BaTiO3 ALD Process onto 200 mm Wafer. *ECS Transactions*, **2006**, 1, 137-141	1	8
11	Atomic Layer Deposition of Intermetallic Co3Sn2 and Ni3Sn2 Thin Films. *Advanced Materials Interfaces*, **2019**, 6, 1801291	4.6	8
10	Submicron fibers as a morphological improvement of amorphous zirconium oxide particles and their utilization in antimonate (Sb(v)) removal.. *RSC Advances*, **2019**, 9, 22355-22365	3.7	6
9	Nickel Germanide Thin Films by Atomic Layer Deposition. *Chemistry of Materials*, **2019**, 31, 5314-5319	9.6	5
8	Crystal structures and thermal properties of some rare earth alkoxides with tertiary alcohols. *Journal of Thermal Analysis and Calorimetry*, **2011**, 105, 61-71	4.1	5
7	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl2(TMPDA) and Tert-Butylhydrazine as Precursors. *Physica Status Solidi (A) Applications and Materials Science*, **2019**, 216, 1900058	1.6	4
6	Highly Material Selective and Self-Aligned Photo-assisted Atomic Layer Deposition of Copper on Oxide Materials. *Advanced Materials Interfaces*, **2021**, 8, 2100014	4.6	3
5	Alkylsilyl compounds as enablers of atomic layer deposition: analysis of (Et3Si)3As through the GaAs process. *Journal of Materials Chemistry C*, **2016**, 4, 449-454	7.1	2
4	Atomic layer deposition of cobalt(II) oxide thin films from Co(BTSA)2(THF) and H2O. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 010908	2.9	1
3	Novel electroblowing synthesis of tin dioxide and composite tin dioxide/silicon dioxide submicron fibers for cobalt(ii) uptake.. *RSC Advances*, **2021**, 11, 15245-15257	3.7	0
2	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. *Dalton Transactions*, **2021**, 50, 13264-13275	4.3	
1	Molecular Layer Deposition of Thermally Stable Polybenzimidazole-Like Thin Films and Nanostructures. *Advanced Materials Interfaces*,2200370	4.6	